

**Notice of References Cited**Application No.  
**09/207,546**

Applicant(s)

**DeGendt et al**

Examiner

**Shamim Ahmed**

Group Art Unit

**1746**

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*		DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS
	A	5,560,857	10/1996	Sakon et al	510	175
	B	6,080,531	6/2000	Carter et al.	430	329
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	K					
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	M					

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*		DOCUMENT NO.	DATE	COUNTRY	NAME	CLASS	SUBCLASS
	N						
	O						
	P						
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**NON-PATENT DOCUMENTS**

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	U	Ohmi et al., "Native Oxide Groth and Organic Impurity Removal on Si Surface with Ozone-Injected Ultrapure Water." Journal of Electrochemical Society, vol.140, No.3, pp.804-810.	3/1993
x	V	K.Sehested et al., "Decomposition of Ozone in Aqueous Acetic Acid Solution (pH 0-4)" J. Phys. Chem, 96, pp. 1005-1009.	1992
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	X	Werner Kern, "Handbook of Semiconductor Water Cleaning Technology" pages 49-52.	1993

\* A copy of this reference is not being furnished with this Office action.  
(See Manual of Patent Examining Procedure, Section 707.05(a).)